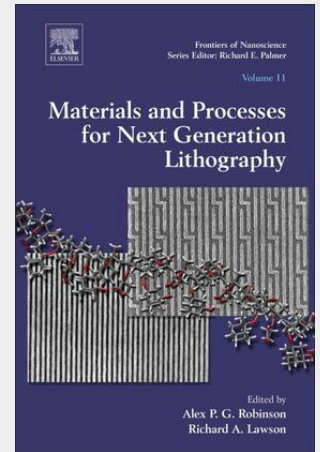


## Materials and Processes for Next Generation Lithography

As the requirements of the semiconductor industry have become more demanding in terms of resolution and speed it has been necessary to push photoresist materials far beyond the capabilities previously envisioned. Currently there is significant worldwide research effort in to so called Next Generation Lithography techniques such as EUV lithography and multibeam electron beam lithography. These developments in both the industrial and the academic lithography arenas have led to the proliferation of numerous novel approaches to resist chemistry and ingenious extensions of traditional photopolymers. Currently most texts in this area focus on either lithography with perhaps one or two chapters on resists, or on traditional resist materials with relatively little consideration of new approaches. This book therefore aims to bring together the worlds foremost resist development scientists from the various community to produce in one place a definitive description of the many approaches to lithography fabrication.

**166,50 €**

155,61 € (zzgl. MwSt.)

*Lieferfrist: bis zu 10 Tage***Artikelnummer:** 9780081003541**Medium:** Buch**ISBN:** 978-0-08-100354-1**Verlag:** Elsevier Science & Technology**Erscheinungstermin:** 18.11.2016**Sprache(n):** Englisch**Auflage:** Erscheinungsjahr 2016**Produktform:** Gebunden**Gewicht:** 1470 g**Seiten:** 634**Format (B x H):** 193 x 242 mm